PHARMACEUTICALS

HALO

5. Itraconazole

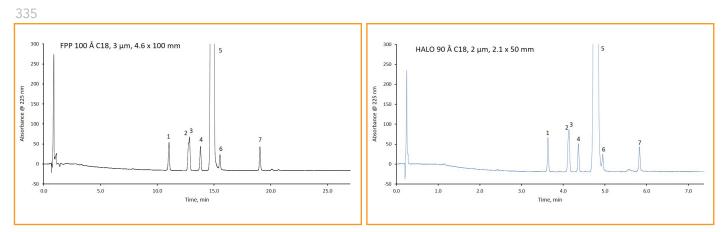
6.

7.

n-Butyl isomer

Didioxolanyl analog

USP Itraconazole System Suitability Comparison



TEST CONDITIONS:

Column: FPP 100 Å C18, 3 µm, 4.6 x 100 mm **Column:** HALO 90 Å C18, 2 µm, 2.1 x 50 mm **Part Number:** 91812-402 Mobile Phase A: 27.2 g/L of Tetrabutylammonium Hydrogen Sulfate in Water Mobile Phase B: ACN Flow Rate: 1.5 mL/min (4.6 mm) 0.5 mL/min (2.1 mm) Pressure: 307 bar/4.6 mm 455 bar/2.1 mm Temperature: 30°C Detection: UV 225 nm, PDA **Injection Volume:** 10 µL (4.6 mm) 1 µL (2.1 mm) Sample Solvent: 0.4% HCl in Methanol Data Rate: 100 Hz Gradients: Response Time: 0.025 sec. FPP C18, 3 µm 4.6 x 100 mm: %B Flow Cell: 1 µL Time 0.00 20 Instrument: Shimadzu Nexera X2 2.00 20 22.00 50 27.00 50 HALO 90 Å C18 2 µm 2.1 x 50 mm: Time %B 0.00 20 0.55 20 50 6.00 7.37 50

PEAK IDENTITIES

- 1. 4-Triazolyl Isomer
- 2. Propyl analog
- 3. Isopropyl analog
- 4. Epimer

Itraconazole is an antifungal medication used for the treatment of various fungal and yeast infections. With the newly approved <621> guidance for allowable changes to USP gradient methods, the method for itraconazole system suitability which was official as of 01-May-2020 from USP can be optimized to save time, reduce solvent consumption, and reduce sample if needed. The method specifies a 4.6 x 100 mm, 3 μ m L1 column. By changing to a shorter length and smaller ID column with smaller particle size (HALO 90 Å, 2 µm, 2.1 x 50 mm), the total run time is reduced by more than 3 times and solvent consumption is reduced by 11 times. Even with these changes, the HALO® column passes the system suitability requirement of peakto-valley ratio by 2 times the minimum. Additionally, the amount of sample injected is reduced from 10 μ L to 1 μ L. HALO[®] Fused-Core[®] technology enables USP gradient methods to be optimized for both time and solvent savings.

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